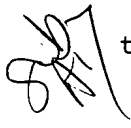


WHAT IS CLAIMED IS:

1. A transfer apparatus for a semiconductor process, comprising:

an articulated arm unit attached to a support base  
5 to be stretchable/retractable within a horizontal plane, the articulated arm unit having a distal end arm which reciprocates in a first direction when the articulated arm unit stretches and retracts;

a support member arranged on the distal end arm to  
10 support a target substrate, the support member being attached to the distal end arm to be reciprocatable in the first direction;

 a main driving mechanism configured to stretch/retract the articulated arm unit; and

15 a sub-driving mechanism configured to reciprocate the support member relative to the distal end arm.

2. The apparatus according to claim 1, wherein the support member reciprocates relative to the distal end arm, while the articulated arm unit stretches and  
20 retracts.

3. The apparatus according to claim 2, wherein the sub-driving mechanism is mechanically connected to the main driving mechanism, such that reciprocation of the support member is performed in accordance with  
25 stretching/retracting of the articulated arm unit.

4. The apparatus according to claim 3, wherein the sub-driving mechanism includes a pair of pulleys

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axially supported by the distal end arm, and a belt extending between the pair of pulleys, the belt being connected to the support member.

5        5. The apparatus according to claim 3, wherein the sub-driving mechanism includes a pair of sprockets axially supported by the distal end arm, and a chain extending between the pair of sprockets, the chain being connected to the support member.

10       6. The apparatus according to claim 3, wherein the sub-driving mechanism is connected to the main driving mechanism through a speed-increasing device.

15       7. The apparatus according to claim 1, further comprising a controller configured to drive the sub-driving mechanism independently of the main driving mechanism.

20       8. The apparatus according to claim 7, wherein the sub-driving mechanism includes a piston cylinder disposed on the distal end arm, and a piston rod reciprocated by the piston cylinder, the piston rod being connected to the support member.

25       9. The apparatus according to claim 7, wherein the sub-driving mechanism includes a ball screw disposed on the distal end arm, a motor disposed on the distal end arm to apply a rotational driving force to the ball screw, and a ball nut engaging with the ball screw and connected to the support member.

10. The apparatus according to claim 1, further

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comprising a pair of temporary shelves configured to support the target substrate, and disposed to sandwich the support member when the articulated arm unit and the support member retract, and a vertical driving mechanism configured to vertically drive the support member and the temporary shelves relative to each other in order to transfer the target substrate therebetween.

11. The apparatus according to claim 10, wherein the articulated arm unit is rotatable within a horizontal plane relative to the support base, and the transfer apparatus further comprises a rotational driving mechanism configured to rotate the articulated arm unit.

12. A transfer apparatus for a semiconductor process, comprising:

an articulated arm unit attached to a support base to be stretchable/retractable within a horizontal plane, the articulated arm unit having a distal end arm which reciprocates in a first direction when the articulated arm unit stretches and retracts, the articulated arm unit being rotatable within a horizontal plane relative to the support base;

a support member arranged on the distal end arm to support a target substrate;

a pair of temporary shelves configured to support the target substrate, and disposed to sandwich the

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support member when the articulated arm unit retracts,  
a main driving mechanism configured to  
stretch/retract the articulated arm unit;

a rotational driving mechanism configured to  
5 rotate the articulated arm unit; and

927 a vertical driving mechanism configured to  
vertically drive the support member and the temporary  
shelves relative to each other in order to transfer the  
target substrate therebetween.

10 13. An accommodating apparatus for a semiconductor  
process, comprising:

an airtight chamber;

a worktable with a mount surface to support a  
target substrate disposed in the chamber, the target  
15 substrate being loaded and unloaded, by a transfer  
apparatus, onto and from the worktable;

a set of first lifters and a set of second lifters  
configured to assist loading/unloading of the target  
substrate onto/from the mount surface, the set of first  
20 lifters and the set of second lifters providing support  
levels at different heights for the target substrate;  
and

a lifter driving mechanism for vertically driving  
the first and second lifters relative to the worktable,  
25 wherein the sets of first and second lifters are  
disposed to surround the worktable,

wherein the first and second lifters respectively

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15. The apparatus according to claim 13, wherein the apparatus is constituted as a semiconductor processing apparatus, and further comprises:

a table driving mechanism for moving the worktable between lower and upper positions, the target substrates being loaded and unloaded, by a transfer apparatus, onto and from the worktable when the worktable is at the lower position, and the target substrate being processed when the worktable is at the upper position;

a supply system with a supply port disposed immediately above the worktable, which is at the upper position, to supply a process gas into the chamber; and

an exhaust system with an exhaust port disposed immediately under the worktable, which is at the lower position, to evacuate an interior of the chamber, and

wherein the sets of first and second lifters are disposed to surround the worktable, which is at the lower position.

16. A semiconductor processing system comprising:

an airtight process chamber;

a worktable with a mount surface to support a target substrate disposed in the process chamber;

a supply system configured to supply a process gas into the process chamber;

an exhaust system configured to evacuate an interior of the process chamber by vacuum;

an airtight transfer chamber connected to the process chamber through a gate; and

a transfer apparatus disposed in the transfer

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chamber to load/unload the target substrate into/from the process chamber, the transfer apparatus comprising an articulated arm unit attached to a support base to be stretchable/retractable within a horizontal plane, the articulated arm unit having a distal end arm which reciprocates in a first direction when the articulated arm unit stretches and retracts;

10 a support member arranged on the distal end arm to support the target substrate, the support member being attached to the distal end arm to be reciprocatable in the first direction;

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a main driving mechanism configured to stretch/retract the articulated arm unit; and

15 a sub-driving mechanism configured to reciprocate the support member relative to the distal end arm.

17. The system according to claim 16, wherein the transfer apparatus further comprises a pair of temporary shelves configured to support the target substrate, and disposed to sandwich the support member when the articulated arm unit and the support member retract, and a vertical driving mechanism configured to vertically drive the support member and the temporary shelves relative to each other in order to transfer the target substrate therebetween.

25 18. The system according to claim 16, further comprising:

a set of first lifters and a set of second lifters

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disposed to surround the worktable and configured to assist loading/unloading of the target substrate on/from the mount surface, the set of first lifters and the set of second lifters providing support levels at  
5 different heights for the target substrate; and

a lifter driving mechanism for vertically driving the first and second lifters relative to the worktable.

19. The system according to claim 16, wherein the support member reciprocates relative to the distal end arm, while the articulated arm unit stretches and retracts.  
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20. The system according to claim 16, further comprising a controller configured to drive the sub-driving mechanism independently of the main driving  
15 mechanism.

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